

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3841	((method or process or manufactur\$3 or produc\$3 or form\$3 or mak\$3) with ((nanoparticle or microparticle or nanocrystal) near3 (In or Zn or Sn or indium or (metal near oxide) or zinc or tin)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/16 15:11
L2	10	1 and (THF or tetrahydrofuran) and (precursor same (cyclopentadiene or cyclopentadienyl or dicyclohexyl or diemethylamide or dicyclopentadiene or dicyclopentadienyl))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/16 15:14
L3	2	("2004115124").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/04/16 15:32
L4	2	("20040115124").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/04/16 15:32
S1	0	(yang near2 zhizhong).in. or (liu near2 xuening).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 14:07
S2	231	((method or process or manufactur\$3 or produc\$3 or form\$3 or mak\$3) with (nanoparticle or microparticle)) and (organometallic near precursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 14:10
S3	1	S2 and (ligand or (aliphatic near3 compound)) and ((oxidiz\$2 or oxidis\$3) near agent)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 14:12
S4	2	("6562403").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/04/10 14:13

S5	7	((method or process or manufactur\$3 or produc\$3 or form\$3 or mak\$3) with (nanoparticle or microparticle) with (colloidal near\$3 solution)) and (organometallic near precursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 14:40
S6	564	(423/592.1).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/04/10 15:12
S7	50	S6 and ((method or process or manufactur\$3 or produc\$3 or form\$3 or mak\$3) with (nanoparticle or microparticle))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 15:12
S8	12	S7 and (organometallic)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 15:13
S9	0	S8 and ((oxidiz\$2 or oxidis\$3) near agent)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 15:33
S10	0	S7 and ((oxidiz\$2 or oxidis\$3) near agent)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 15:33
S11	4	S7 and ((oxidiz\$3 or oxidis\$3) near agent)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/10 15:34
S12	1	"bis(bis(dimethylamide))" or "tin dicyclopentadienyl" or [Sn("C.sub.5H.sub.5").sub.2" or Sn(N("CH.sub.3").sub.2")".sub.2" or "indium cyclopentadienyl" or In("C.sub.5.H.sub.5")]	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:23
S13	37	(dicyclopentadienyl or dicyclopentadienyl or [Sn("C.sub.5H.sub.5").sub.2" or Sn(N("CH.sub.3").sub.2")".sub.2" or In("C.sub.5.H.sub.5")]) with precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:25
S14	14	(dicyclopentadienyl or dicyclopentadienyl dimethylamide or [Sn("C.sub.5H.sub.5").sub.2" or Sn(N("CH.sub.3").sub.2")".sub.2" or In("C.sub.5.H.sub.5")]) near\$3 precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:26

S15	0	(dicyclopentadienyl or dicyclohexyl dimethylamide or [Sn("C.sub.5H.sub.5").sub.2" or Sn(N("CH.sub.3").sub.2").sub.2]".sub.2" or In ("C.sub.5.H.sub.5")) near3 precursor near (tin or Indium or Sn or Tin or Zn or zinc)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:28
S16	2	(dicyclopentadienyl or dicyclohexyl dimethylamide or [Sn("C.sub.5H.sub.5").sub.2" or Sn(N("CH.sub.3").sub.2").sub.2]".sub.2]".sub.2" or In ("C.sub.5.H.sub.5")) with precursor with (tin or Indium or Sn or Tin or Zn or zinc)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:28
S17	4960	((zinc or Zn) with dicyclohexyl) or Zn("C.sub.6H.sub.11").sub.2" or "tin bis(bis(dimethylamide))" or [Sn(N("CH.sub.3").sub.2").sub.2]".sub.2" or ((tin or Sn) with dicyclopentadienyl) or Sn("C.sub.5H.sub.5").sub.2" or ((indium or In) with cyclopentadienyl) or In("C.sub.5H.sub.5") or "InC.sub.5H.sub.5"	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:32
S18	88	((zinc or Zn) with dicyclohexyl) or Zn("C.sub.6H.sub.11").sub.2" or "tin bis(bis(dimethylamide))" or [Sn(N("CH.sub.3").sub.2").sub.2]".sub.2" or ((tin or Sn) with dicyclopentadienyl) or Sn("C.sub.5H.sub.5").sub.2" or ((indium or In) with cyclopentadienyl) or In("C.sub.5H.sub.5") or "InC.sub.5H.sub.5") with precursor?	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:33
S19	8	((method or process or manufactur\$3 or produc\$3 or form\$3 or mak\$3) with (nanoparticle or microparticle)) and S18	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:33
S20	8	((method or process or manufactur\$3 or produc\$3 or form\$3 or mak\$3) with (nanoparticle or microparticle or nanocrystal)) and S18	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2008/04/14 13:33

4/16/2008 5:25:02 PM

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